

SEP 08 2008

**AMENDMENTS TO THE CLAIMS:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A mask comprising:

a first thin film portion for exposure that has a transmission portion and a non-transmission portion of a beam for exposure in a predetermined pattern;  
a thick film portion that is formed around said first thin film portion for exposure and that supports said first thin film portion for exposure; and

a second thin film portion for inspection that is formed at a distance from said first thin film portion for exposure in a portion of said thick film, and that has a transmission portion and a non-transmission portion of said beam for exposure;

wherein said first thin film portion for exposure comprises a first vulnerable sub-portion that has a highest probability of pattern damage within said first thin film portion for exposure; and

wherein said second thin film portion for inspection comprises a second vulnerable sub-portion that has a highest probability of pattern damage within said second thin film portion for exposure, the second vulnerable sub-portion having a higher probability of pattern damage than said first vulnerable sub-portion.

2. (Currently Amended) A mask as set forth in claim 1, wherein

thickness and material composition of said second thin film portion for inspection ~~are equal to those of~~ and said first thin film portion for exposure ~~are substantially the same.~~

Appl. No. 10/518,345  
Amdt. Dated September 4, 2008  
Reply to Office action of June 11, 2008

3. (Currently Amended) A mask as set forth in claim 1, wherein  
said non-transmission portion comprises portions comprise a thin film, and  
said transmission portion comprises portions comprise an aperture formed in said thin film.

4. (Currently Amended) A mask as set forth in claim 1, wherein  
said transmission portion comprises portions comprise a thin film, and said  
non-transmission portion comprises portions comprise a beam scatterer for exposure formed  
on said thin film.

5. (Currently Amended) A mask as set forth in claim 1, wherein  
said thin film portion for exposure is comprised of a pattern repeated a  
plurality of times corresponding to the number of individual patterned devices the mask is  
intended to form, and said thin film portion for inspection is comprised of a pattern repeated  
one or more times corresponding to a desired number of test cases;

wherein an the area of a single pattern formed in said second thin film portion for  
inspection is larger than a single pattern formed in said first thin film portion for exposure,  
and the flexure of said second thin film portion for inspection is bigger than that of said first  
thin film portion for exposure.

6. (Currently Amended) A mask as set forth in claim 1, wherein  
said second thin film portion for inspection has said transmission portions  
portion comprised of a pattern of which line width is varied is different each other.

7. (Currently Amended) A mask as set forth in claim 1, wherein

Appl. No. 10/518,345  
Amdt. Dated September 4, 2008  
Reply to Office action of June 11, 2008

said second thin film portion for inspection has portions in which the density of said transmission portion comprised of a pattern having a varied pattern density is different each other.

8. (Canceled)

9. (Currently Amended) A mask as set forth in claim [[8]] 1, wherein said second vulnerable sub-portion comprises a pattern of which line width is narrower than a pattern of said first vulnerable sub-portion.

10. (Currently Amended) A mask as set forth in claim [[8]] 1, wherein the density of said transmission portion of said second vulnerable sub-portion is higher than the density of said transmission portion of said first vulnerable sub-portion.

11. - 28. (Canceled)